

Tape-out Review Form (for Full-custom IC)

The Tape-out Review Form is intended to remind designers to demonstrate design concepts and comprehend design, simulation, layout verification, and tape-out notes. It is hoped that the success rate of IC design and comprehensive learning results can be improved. As a result, the adviser and designer are asked to double-check that the requirements in this form were noted during the chip design process. If the design content and completion of the Tape-out Review Form are found to be inconsistent during review, the chip tape-out manufacturing qualifications will most likely be canceled.

Project name: _____ Example of TSRI Tape-out Review Form _____
 Name of Top Cell: _____ TSRI EXEMPLE _____
 Process name: _____ T18 _____

1 Circuit overview:

- 1-1. Work voltage: _____ 3.3V _____
 1-2. Work frequency: _____ 20MHz _____
 1-3. Power consumption: _____ 3mW _____
 1-4. Is ARM CPU IP provided by TSRI used? _____ No _____
 What type of CPU is used? (ARM7TDMI or ARM926EJ) _____
 1-5. Is this the initial circuit architecture that your laboratory has designed? Yes (proceed to 2-1)
No (proceed to 1-5-1) _____
 1-5-1. What are the causes of previous subpar circuit measurement work or performance? _____

 1-5-2. What changes have been made to previous errors? _____

2 Circuit simulation considerations

- 2-1. Which spice model simulation statuses have been used in SS, SF, TT, FS, and FF? Each of the five corners has been simulated. _____
 2-2. Have the scenarios that affect circuit work when voltage changes are +/-10% been simulated? 2.97V~3.63V complies with the design. _____
 2-3. In what manner are variations in temperature accounted for in their effects? Initiate simulation with temperatures ranging from 0 to 100 degrees. _____
 2-4. In what manner are process variations in capacitance and resistance accounted for in their effects? The maximum and minimum variation values should be substituted into the simulation. _____
 2-5. During simulation, are the effects of the IO PAD and bonding wire included, as well as taking into account the test instrument load and other effects? Yes _____
 2-6. Are LPE and post layout simulation performed? _____ Yes _____ Software used: Calibre &

HSPICE

3 Power Line layout considerations

- 3-1. What is the width of the power line? 20um
- 3-2. Is power line current density taken into account? Yes
- 3-3. Are the parasitic resistance and capacitance of the metal line taken into account?
Yes

4 DRC, LVS

- 4-1. Is it confirmed that the most recent versions of the DRC and LVS Command Files are in use?
Yes
- 4-2. Are the DRC and LVS of whole chips performed? Yes
- 4-3. Have flat DRC and hierarchical DRC been verified during DRC verification? Yes
- 4-4. Is the density rule taken into account? Yes Is the filling method manual dummy cell filling of dummy generation filling? manual dummy cell filling until the density rules are complied.
- 4-5. Are there any errors in the internal circuit or pad connection wiring aside from the DRC error on the pad? No
What are the causes of errors? _____
- 4-6. During the LVS process, does the pin and component match? Yes What is the reason for the mismatch? _____
- 4-7. Verify whether a short circuit, displacement, or broken circuit is present between the pads.
Yes
- 4-8. Verify whether the area of the bare pad is disproportionately small, whether windows are ajar, and whether there are any measurement considerations. Yes

5 ESD I/O PAD considerations

- 5-1. Create instance is the approach used to add I/O Pad, and copy or flatten destruction of instance structure are not used. Yes
- 5-2. In the IC core, wiring from pad only extends to the outermost edge, not excessively covering Pad. Yes
- 5-3. Is TSMC I/O PAD used (D35 process fill-out)? Yes
- 5-3-1. The personalized design cell name is not the same as any of the pad cell names provided by TSMC. Please make a thorough check. It has been verified.

6 Analog-Mixed signal circuit layout considerations (analog-filled out by the mixed signal circuit designer)

- 6-1. Layout symmetry and consistency considerations
- 6-1-1. Is the OP (comparator) input stage symmetrical? Yes

- 6-1-2. Is the dummy cell technique used in symmetrical components during layout?
Yes _____
- 6-1-3. Is a concentric circle layout used for symmetrical capacitors? _____ Yes _____
- 6-1-4. Does the symmetrical unit capacitor have 45-degree angles cut on its edges?
Yes _____
- 6-1-5. Is the unit area of the symmetrical capacitor consistent? _____ Yes _____
What is the size of the area of the unit capacitor? _____ 33 _____ μm x _____ 33 _____ μm
What is the size of the unit capacitance value? _____ 1 _____ pF
Are the upper and lower bipolar plates connected correctly? _____ Yes _____
- 6-1-6. What material is a resistor made of? _____ Poly2 _____
What is the size of the unit resistance value? _____ 50 Ω _____
- 6-2. Circuit noise layout considerations (filled out by the mixed signal circuit designer).
- 6-2-1. Will the power lines of analog and digital be separated? _____ Yes _____
- 6-2-2. Is a guard ring being used to isolate the analog area? _____ Yes _____
- 6-2-3. Is a guard ring used to isolate the digital area? _____ Yes _____
- 6-2-4. Is the shield technique used for the sensitive line? _____ Yes _____
- 6-2-5. Are the analog guard ring and shield connected to a clean potential?
Yes _____
- 6-2-6. Is the sensitive line shortened as much as possible to avoid crossing the noise (clock) line? _____ Yes _____

7 MEMS design considerations (filled out by the MEMS designer)

- 7-1. Please briefly describe post-processes undertaken: _____ First, engage in etching and then incorporate carbon nanotubes. _____
- 7-2. Location of post-process operations: _____ Asia Pacific Microsystems, Inc. _____
- 7-3. Is the person performing the tape-out task legally authorized to operate the process equipment?
Yes _____ If there is currently no legal authorization to operate the process equipment, can legal authorization be obtained before retrieving the chips? _____ Yes _____
- 7-4. Is the individual performing the tape-out task experienced in operating the process equipment?
Yes _____
- 7-5. Are post-process parameters available (pressure, temperature, flow, etc.)? _____ Yes _____
- 7-6. Has the post-process previously been implemented successfully? _____ Yes _____
- 7-7. Will the layout part that violated the design rule have an effect on the microstructure or component operations? _____ No _____
- 7-8. Is the size of the etching hole adequate to suspend structures? _____ Yes _____
- 7-9. What is the range of the component drive voltage? _____ 0~3.3V _____

8 RF Circuit layout considerations (filled out by the RF operation frequency designer):

- 8-1. Which system meets the requirements of the circuit specification? _____ 802.11b/g _____

- 8-2. Explain the source of the passive component model. Obtained from EM simulation.
- 8-3. Simulation software (more than one type is possible) ADS Circuit
- 8-4. Have the respective blocks of system-integrated chips undergone tape-out and met the expected specifications (the chip is the system integrator answer and the process MPW run code)?
- 8-5. Layout considerations:
- 8-5-1. Is the component layout method consistent with the layout provided by the model provider? Yes
- 8-5-2. Are ground and voltage sources uniform? Yes
- 8-5-3. Are current carrying capacities of components and wiring factors to be considered? Yes
- 8-5-4. Is the wiring excessively long and thin? No
- 8-5-5. Does the PAD layout take measurement considerations into account? Yes
- 8-5-6. Are the pad and bond wire effects taken into account? Yes
- 8-6. Please specify if some of the errors are special considerations during the DRC verification process.
 The CTM.R2 density is inadequate, which is listed as an allowable error in accordance with TSRI regulations.
- 8-7. Has the comparison of inductors, capacitors, or other special components been handled during the LVS verification process? Please elaborate.
 There is a self-made inductor on the circuit, and the short-circuit inductor undergoes an LVS comparison. After comparison, no error was found.
- 8-8. Is the measurement method on wafer, on PCB or in package? Also explain notes during measurement and the measurement location.
 For the measurement of On Wafer, the measurement location is a laboratory with a high CIC frequency.

9 GIPD circuit layout consideration (filled out by the GIPD, GIPD/T18 designer):

- 9-1. The issue of non-flat GIPD processes is likely to result in insertion measurement failure. (Please consult Attachment A for the environment and layout document pertaining to GIPD processes.) The design of the insertion pad has incorporated a higher degree of flatness in the insertion area to facilitate insertion measurements. Has it been verified? The pad has been thoroughly checked, and the explanation document has been thoroughly read.
- 9-2. The following is filled out by the GIPD/T18 designer:
- 9-2-1. Have 1. the overall layout file (including the T18, bumper, and GIPD layers) and 2. the T18+bumper layout file been submitted for the layout? Furthermore, an independent mirror flip is absent. Has it been verified? Yes
- 9-2-2. The Bumper layout file is provided by CIC and is modified independently modified or innovative bumper layout. Has it been verified? Yes

- 9-2-3. The quantity of bumpers is inadequate to support the T18 chip load. The exact number of bumpers required to correspond with the length has been carefully computed. Has it been verified? _____ Yes _____
- 9-2-4. The T18 area must be greater than 1mm*1mm for CIPD/T18 integration chips, and the insertion pad distance from the T18 chips must be a minimum of 400um. Has it been verified? _____ Yes _____
- 9-2-5. Top Metal is used to create GIPD/T18 integration chips and layout files that meet the fiducial mark required for flip chip packaging per DRC specifications. Furthermore, the layout plan includes detailed markings. Has it been verified? _____ Yes _____

10 HV circuit design consideration (filled out by the T18HVG2/T25HVG2 designer):

- 10-1. Have the three DRC verifications been approved?
- Wire-bond Rule ■ Main Design Rule ■ Antenna Rule
- 10-2. The OD/PO/Metal Density rule has been approved.
- Yes No (Application cases will not be accepted if the density is not complaint with the specifications.)
- 10-3. (0,0) are the coordinates of the whole chip's lower left corner.
- Yes No
- 10-4. Select the whole chip using the ref (drawing) (0;0) layer.
- Yes No
- 10-5. Are high-voltage transistors, BJTs, diodes, resistors and other components utilized in the circuit?
- No
 - High voltage transistors: _____
 - BJT: _____
 - Diodes: _____
 - Resistance: _____
 - Others: _____
- 10-6. Is there a protective circuit design?
- No ■ over-voltage protection ■ over-current protection ■ over-temperature protection ■ ESD protection circuit
 - Other protections and considerations: _____
- 10-7. What is the circuit type?
- High-voltage component structures and characteristics ■ power conversion circuit ■ LED drive ■ detection and protection ■ topology control ■ energy extraction biomedical applications others: _____

11 T50GaN circuit design considerations (filled out by the T50GaN designer):

- 11-1. Have the following DRC verifications been approved?
- Main Design Rule

11-2. (0,0) are the coordinates of the whole chip's lower left corner.

- Yes No

11-3. Components used in the circuit:

- No

■ Components used: _____

11-4. Is there a protective circuit design?

- No ■ over-voltage protection ■ over-current protection ■ over-temperature protection ■ ESD protection circuit

Other protections and considerations: _____

11-5. What is the circuit type?

- High-voltage component structures and characteristics ■ power conversion circuit ■ high-speed drive circuit ■ EV related applications ■ high-power wireless charging ■ radar and laser related applications others: _____

12 U18 circuit design considerations (filled out by U18 designers)

12-1. Have the following DRC verifications been approved?

- Base Rule ■ ANT Rule ■ DIFF Rule ■ ESD Rule ■ Latch-up Rule
- Metal Rule ■ OPC Rule ■ PAD Rule ■ POLY Rule

12-2. In the CMOS layout, has the DMBK Layer been selected?

- PO_CAD(DK) ■ DIFF_CAD(DK) ■ M1_CAD(DK) ■ M2_CAD(DK) ■ M3_CAD(DK) ■ M4_CAD(DK) ■ M5_CAD(DK) ■ M6_CAD(DK)

12-3. In the MEMS layout, in addition to the above-mentioned 12-2 DMBK Layer, has the M7 DMBK Layer been selected?

- M7_CAD(DK)

12-4. The illustrated nine test results of the DRC Rule should be enumerated and explained individually in the design content e-file. Additionally, consult the page for the Design Rules Check (DRC).

- It has been verified.

12-5. If it is necessary to deviate design requirements from the DRC, please fill out the Application Form for Deviation from DRC to the U18 process engineers through email as soon as the DRC verification results are available.

- It has been verified.

12-6. For the Dummy Layer, it is advisable to utilize PO_CAD(Dy), DIFF_CAD(Dy), M1_CAD(Dy), M2_CAD(Dy), M3_CAD(Dy), M4_CAD(Dy), M5_CAD(Dy), M6_CAD(Dy), and M7_CAD(Dy) instead of the DMBK Layer.

- It has been verified.

13 ARM926EJ or ARM7TDMI CPU IP is used.

13-1. If ARM926EJ /ARM7TDMI CPU IP are used, please provide the information below to submit

a Design ID application to the ARM manufacturer.

CPU type used (ARM926EJ or ARM7TDMI): ARM926E

The number of metal layers used: 6

The cell name of ARM926EJ /ARM7TDMI Macro during layout: TEST

Is this chip a revision, or is it identical to those that were previously taped out? No

If it is a revised version, the next tape-out chip number is: _____

Reason for revising the version: (such as bug correction) _____

14 Other considerations

14-1. Is the output measurement point during testing taken into account? Yes

14-2. Is the modifiability of circuits taken into account? (such as laser cut equipment) Yes

Signature of designer: Wang Hsiao-Ming Name of advisor: Li Ta-Ming

(Please ensure that this document is fully completed and submit the electronic file. No physical copy is required for submission.)